ALTERNATING PHASE SHIFT MASK AND METHOD FOR FABRICATING THE ALIGNMENT MONITOR

ABSTRACT

A new process for fabricating an alternating phase-shifting photomask having an alignment monitor is described. An opaque layer is provided overlying a substrate. The opaque layer is patterned to provide a mask pattern. A phase-shifting pattern is formed on the substrate wherein a portion of the phase-shifting pattern comprises an alignment monitor whereby alignment between the mask pattern and the phase-shifting pattern can be tested.

(Figure 3A)